ABSTRACT OF THE DISCLOUSURE

Low magnification factor pattern image data D1 including the center of the observational position is acquired by adjusting an observation position using a pattern observation device 3 so that the center of observation of prescribed locations of a pattern enter the observational field of view at a low magnification factor. Data D4 for an offset amount caused by errors for the stage 2 is obtained by comparing the edge line segment data D2 based on low magnification factor pattern image data D1 to corresponding CAD line segment data D3. The stage 2 is moved relatively to compensate the offset amount to align the observational field of view of the pattern observation device 3 precisely at the specified pattern portion.